

# Hisashi Ohsaki

## List of Publications by Year in descending order

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47  
papers

800  
citations

516561

16  
h-index

526166

27  
g-index

47  
all docs

47  
docs citations

47  
times ranked

829  
citing authors

#	ARTICLE	IF	CITATIONS
1	Sliding Behavior of Water Droplets on Flat Polymer Surface. Journal of the American Chemical Society, 2006, 128, 743-747.	6.6	61
2	Global market and technology trends on coated glass for architectural, automotive and display applications. Thin Solid Films, 1999, 351, 1-7.	0.8	59
3	Super-hydrophobic photocatalytic coatings utilizing apatite-based photocatalyst. Thin Solid Films, 2006, 502, 108-111.	0.8	57
4	Photocatalytic efficiency of TiO <sub>2</sub> /SnO <sub>2</sub> thin film stacks prepared by DC magnetron sputtering. Vacuum, 2004, 74, 723-727.	1.6	52
5	The underlayer effects on the electrical resistivity of Ag thin film. Thin Solid Films, 2006, 502, 223-227.	0.8	49
6	Optical properties of multilayers composed of silver and dielectric materials. Thin Solid Films, 2003, 442, 212-216.	0.8	45
7	Photocatalytic properties of SnO <sub>2</sub> /TiO <sub>2</sub> multilayers. Thin Solid Films, 2006, 502, 138-142.	0.8	44
8	High rate sputter deposition of TiO <sub>2</sub> from TiO <sub>2</sub> target. Thin Solid Films, 1999, 351, 57-60.	0.8	39
9	TiO <sub>2</sub> sputter for high rate deposition of TiO <sub>2</sub> . Vacuum, 2000, 59, 836-843.	1.6	37
10	High rate deposition of TiO <sub>2</sub> by DC sputtering of the TiO <sub>2</sub> target. Thin Solid Films, 2001, 392, 169-173.	0.8	36
11	A new layer system of anti-reflective coating for cathode ray tubes. Thin Solid Films, 1999, 351, 235-240.	0.8	33
12	High-rate deposition of SiO <sub>2</sub> by modulated DC reactive sputtering in the transition mode without a feedback system. Thin Solid Films, 1996, 281-282, 213-217.	0.8	26
13	Materialistic Difference in Macroscopic Friction Coefficients of Sputtered Metal Oxide Thin Films Deposited on Glass. Japanese Journal of Applied Physics, 1996, 35, 1862-1867.	0.8	21
14	Preparation and Water Droplet Sliding Properties of Transparent Hydrophobic Polymer Coating by Molecular Design for Self-Organization. Journal of Sol-Gel Science and Technology, 2004, 31, 195-199.	1.1	20
15	Room-temperature crystallization of amorphous films by RF plasma treatment. Thin Solid Films, 2009, 517, 3092-3095.	0.8	20
16	Optical properties of Ag/dielectric-material multilayers. Vacuum, 2004, 74, 555-559.	1.6	17
17	Plasma treatment for crystallization of amorphous thin films. Thin Solid Films, 2006, 502, 63-66.	0.8	17
18	Structural analysis of SiO <sub>2</sub> gel films by high energy electron diffraction. Journal of Sol-Gel Science and Technology, 1994, 2, 245-249.	1.1	14

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19	Enhancement of photocatalytic activity using UV light trapping effect. <i>Vacuum</i> , 2004, 74, 729-733.	1.6	14
20	Room temperature crystallization by RF plasma. <i>Thin Solid Films</i> , 2008, 516, 4490-4494.	0.8	11
21	Room temperature crystallization of indium tin oxide films on glass and polyethylene terephthalate substrates using rf plasma. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2007, 25, 1052-1055.	0.9	10
22	Low resistance AR stack including silver layer. <i>Thin Solid Films</i> , 2003, 442, 153-157.	0.8	9
23	Preparation of Transparent Thin Film of Novel Apatite-based Photocatalyst. <i>Chemistry Letters</i> , 2005, 34, 1666-1667.	0.7	9
24	Preparation of cobalt-titanium dioxide nanocomposite films by combining inverse micelle method and plasma treatment. <i>Materials Letters</i> , 2007, 61, 2173-2177.	1.3	9
25	Multilayered Ordering of the Metal Nanoparticles in Polymer Thin Films under Photoirradiation. <i>Langmuir</i> , 2011, 27, 733-740.	1.6	9
26	Oxidation mechanism of amorphous silicon in air. <i>Journal of Non-Crystalline Solids</i> , 1987, 93, 395-406.	1.5	8
27	DC reactive sputtering of electro-conductive transparent tin suboxide using a Sn-O <sub>2</sub> /Ar system. <i>Thin Solid Films</i> , 1996, 281-282, 223-227.	0.8	8
28	Structure of an extremely thin film of a-SiO <sub>2</sub> . <i>Journal of Non-Crystalline Solids</i> , 1987, 95-96, 1095-1101.	1.5	7
29	Shrinkage of atomic distances in ultrathin a-SiO <sub>2</sub> film. <i>The Philosophical Magazine: Physics of Condensed Matter B, Statistical Mechanics, Electronic, Optical and Magnetic Properties</i> , 1992, 66, 25-36.	0.6	7
30	Fabrication of Mo microcones for volcano-structured double-gate Spindt-type emitter cathodes using triode high power pulsed magnetron sputtering. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2017, 35, .	0.6	7
31	Densimetry of Amorphous Silicon Films by Using a Quartz Oscillator. <i>Japanese Journal of Applied Physics</i> , 1986, 25, 1152-1155.	0.8	6
32	Effects of vacuum ultraviolet light illumination and seeding on crystallization of sol-gel-derived titanium dioxide precursor films using plasma treatment. <i>Surface and Coatings Technology</i> , 2006, 201, 3038-3043.	2.2	6
33	Crystallization of ITO and TiO <sub>2</sub> by RF plasma treatment. <i>Vacuum</i> , 2013, 87, 145-149.	1.6	6
34	Bendable and temperable solar control glass. <i>Journal of Non-Crystalline Solids</i> , 1997, 218, 223-229.	1.5	5
35	Characterization of sputtered triple layer photoactive coating with a glass-like appearance. <i>Thin Solid Films</i> , 2008, 516, 4558-4562.	0.8	5
36	Numerical calculations of elastic scattering amplitudes for high-energy electron scattering by ionized atoms. <i>The Acta Crystallographica Section A, Crystal Physics, Diffractionoretical and General Crystallography</i> , 1980, 36, 316-321.	0.6	4

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37	Structure of the Natural Oxide of Amorphous Silicon. Japanese Journal of Applied Physics, 1986, 25, 1773-1777.	0.8	3
38	High Energy Electron Diffraction Study on Ionic Character of Amorphous SiO <sub>2</sub> . Japanese Journal of Applied Physics, 1986, 25, 1768-1772.	0.8	3
39	Band-selective Mirror Characteristics of Polymer/Metal Multilayer Films. Chemistry Letters, 2011, 40, 1138-1139.	0.7	3
40	Title is missing!. Shinku/Journal of the Vacuum Society of Japan, 2001, 44, 520-527.	0.2	3
41	Anatase TiO <sub>2</sub> Films Crystallized by RF Plasma Treatment. IOP Conference Series: Materials Science and Engineering, 2011, 18, 172004.	0.3	1
42	Formation mechanism of evaporated a-SiO <sub>2</sub> : An approach from the oxidation processes of a-Si. Applied Surface Science, 1988, 33-34, 773-778.	3.1	0
43	Electron Diffraction Analysis of the Structure of SiO <sub>2</sub> Gel-Film. Materials Research Society Symposia Proceedings, 1990, 180, 429.	0.1	0
44	Structural difference of surface and sub-surface native oxides of evaporated amorphous silicon. Journal of Non-Crystalline Solids, 1990, 120, 275-282.	1.5	0
45	Densification of spin-on-glass (SOG) film by RF plasma treatment. IOP Conference Series: Materials Science and Engineering, 2011, 18, 032007.	0.3	0
46	Global market and technology trends on coated glass for architectural, automotive and display applications. , 1999, , 1-7.		0
47	High rate sputter deposition of TiO <sub>2</sub> from TiO <sub>2</sub> target. , 1999, , 85-88.		0